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APR -4 2003

PATENT Customer No. 22,852 Attorney Docket No. 08268.0027

TECHNOLOGY CENTER 2800
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In re Application of:

Sung Gyu PYO

Serial No.: 09/879,204

Filed: June 13, 2001

For:

HEATER BLOCK HAVING

CATALYST SPRAY MEANS

Group Art Unit: 2812

Examiner: Unknow Art Control of the Control

Commissioner for Patents Washington, DC 20231

Sir:

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. § 1.97(b)

Pursuant to 37 C.F.R. §§ 1.56 and 1.97(b), Applicant brings to the attention of the Examiner the documents listed on the attached PTO 1449. This Information Disclosure Statement is being filed before the mailing date of a first Office Action on the merits for the above-referenced application. Copies of the listed documents are attached.

Applicant respectfully requests that the Examiner consider the listed documents and indicate that they were considered by making appropriate notations on the attached form.

The following is a concise statement of relevance of the non-English language documents.

FINNEGAN HENDERSON FARABOW GARRETT & DUNNER些

1300 I Street, NW Washington, DC 20005 202,408,4000 Fax 202.408.4400 www.finnegan.com

1. Korean Patent Laid-Open No. 97-0077163 is directed to a deposition chamber and method for depositing low dielectric constant films. An improved deposition chamber (2) includes a housing (4) defining a chamber (18) which houses a substrate support (14). A mixture of oxygen and SiF₄ is delivered through a set of first nozzles (34) and silane is delivered through a set of second nozzles (34a) into the chamber around the periphery (40) of the substrate support. Silane (or mixture of silane and SiF₄) and oxygen are separately injected into the chamber generally centrally above the substrate from orifices (64, 76). The uniform dispersal of the gases coupled with use of optimal flow rates for each gas results in uniformly low (under 3.4) dielectric constant across the film.

2. Japanese Patent Laid-Open No. 9-181065 is directed to a deposition chamber. The deposition chamber comprising: a housing defining a single vacuum chamber; a substrate support having a substrate support surface within the vacuum chamber, the substrate support surface having a central region and a periphery; a plurality of first gas distributors having first exits opening into the vacuum chamber, the first exits directed generally towards the central region; and a second gas distributor having a second exit spaced apart from and generally overlaying said substrate support surface, said second exit opening directly into the vacuum chamber.

These documents were cited in an Official Action from the Korean Patent Office in related Korean Application No. 00-32397.

This submission does not represent that a search has been made or that no better art exists and does not constitute an admission that each or all of the listed documents are material or constitute "prior art." If the Examiner applies any of the

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1300 I Street, NW Washington, DC 20005 202.408.4000 Fax 202.408.4400 www.finnegan.com documents as prior art against any claim in the application and Applicant determines that the cited documents do not constitute "prior art" under United States law, Applicant reserves the right to present to the office the relevant facts and law regarding the appropriate status of such documents.

Applicant further reserves the right to take appropriate action to establish the patentability of the disclosed invention over the listed documents, should one or more of the documents be applied against the claims of the present application.

If there is any fee due in connection with the filing of this Statement, please charge the fee to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW, GARRETT & DUNNER, L.L.P.

Dated: April 3, 2003

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Bryan S. Latham Reg. No. 49,085

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INFORMATION DISCLOSURE CITATION

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97-0077163	12-1997	Korea			No	
9-181065	7-1997	Japan			No	
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)						
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*Examiner: Initial if reference co through citation if no communication to ap		Date Considered ce considered, whether or not citation is in conformance with MPEP 609; draw line if not in conformance and not considered. Include copy of this form with next in to applicant.		